

## **LISTING OF THE CLAIMS**

This listing of claims will replace all prior versions, and listings, of claims in the application:

### **1. - 24. (Canceled)**

**25. (Currently Amended)** A substrate treating apparatus for removing photoresist film from a substrate by supplying a treating solution thereto, comprising:

a support means including a chuck rotatable by a motor for supporting and spinning said substrate in a horizontal plane;

an ozone water supply means including a nozzle for supplying ozone water having ozone dissolved in deionized water to a spin center on an upper surface of said substrate;

an ultraviolet emitting means including UV lamps and a reflector for emitting ultraviolet light to said substrate, said ultraviolet emitting means emitting ultraviolet light under atmospheric conditions to said substrate from an irradiating position above said support means; and

a controller being structured to rotate said support means supporting said substrate, and to supply said ozone water from said nozzle of said ozone water supply means to ~~[[a]]~~ the spin center of said substrate the controller being structured to control supplying power to said UV lamps to emit ultraviolet light to said ozone water being supplied to said substrate during removal of the photoresist film, in a manner such as to cause the apparatus to generate oxygen radicals by means of the UV lamps, and to remove the photoresist film from the substrate coated with the photoresist film.

**26. (Previously Presented)** An apparatus as defined in claim 25, wherein the ultraviolet light has a wavelength in a range of 242.4 to 300nm.

**27. (Previously Presented)** An apparatus as defined in claim 25, including base adding means for adding a base to the treating solution.

**28. (Previously Presented)** An apparatus as defined in claim 26, including base adding means for adding a base to the treating solution.

**29. - 37. (Canceled)**